

ALIGNMENT SYSTEM AND METHOD USING BRIGHT SPOT AND BOX STRUCTURE

ABSTRACT OF THE DISCLOSURE

5 There is provided a method for aligning a
semiconductor wafer and a mask. A semiconductor wafer is
provided having an alignment mark formed thereon. A mask
is provided having a pattern formed thereon. The mask is
illuminated so as to create a bright spot thereon by a $0-\pi$
10 phase conflict. The alignment mark is aligned with the
bright spot, so as to align the semiconductor wafer with
the mask. Preferably, the method includes the step of
creating the alignment mark on the semiconductor wafer in a
form of a frame. Moreover, preferably, the creating step
15 includes the step of creating the frame to minimize an
impact of film stack variations.